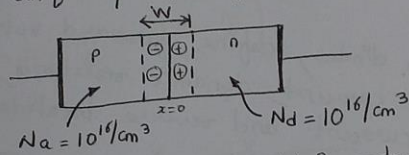


Date: 09/09/2015
 Marks: 20

Time: 1 hour

Note: Attempt any two questions:

Q1. Given is a uniformly doped p-n junction (Si) in thermal equilibrium:-



at $T = 300K$

- Derive the expression for built-in potential (2m)
- From the given information, calculate V_{bi} (1m)
- Draw EBD of given device in equilibrium and under forward applied bias. (2m)
- Find 'w' for zero-applied bias and a reverse bias of 8V. (1m)
- Find max E-field under zero-applied bias. (1m)
- Draw small-signal model for this device. (1m)
- $I = I_0 \left[\exp\left(\frac{V_a}{V_T}\right) - 1 \right]$ is ideal p-n junction diode current. Write formula for I_0 ? what it is called? (1m)

$$V_{bi} = V_T \ln \left(\frac{N_a N_d}{n_i^2} \right)$$

$$V_{bi} = 0.697 \text{ V}$$

$$w = 4.17 \times 10^{-5} \text{ cm } 10 \mu\text{m}$$

$$w = 1.47 \times 10^{-4} \text{ cm } 1.47 \mu\text{m}$$

$$E_m = \frac{-2V_{bi}}{w} = -33.4 \text{ kV/cm}$$

$$I_0 = \left[\frac{2A D_p p_{n0}}{L_p} + \frac{2A D_n n_{p0}}{L_n} \right]$$

Given data:
 $q = 1.6 \times 10^{-19} \text{ C}$
 $n_i = 1.5 \times 10^{10} / \text{cm}^3$
 $\epsilon_{Si} = 11.7 \times 8.854 \times 10^{-14}$

— Turn over —
 (1)

- Q2.
- Explain working and characteristics of N-channel JFET? (5m)
 - For a JFET, g_m is transconductance. (2m)
 Show that: $g_m = -\frac{2}{V_p} I_{DSS} \left(1 - \frac{V_{GS}}{V_p}\right)$
 starting from I_{Dsat} expression.
 - Compare zero and Avalanche breakdown mechanisms (2m)
 - Explain how JFET works as a voltage controlled resistor (with the help of characteristics) (1m)

- Q3.
- For the pn diodes, define forward voltage drop, max forward current, dynamic resistance, reverse saturation current and reverse breakdown voltage (2m)

- Max Electric field in a reverse bias Si pn junction is 3×10^5 v/cm. The doping concentration $N_d = 4 \times 10^{16}/\text{cm}^3$ and $N_a = 4 \times 10^{17}/\text{cm}^3$ (3m)

$V_{bi} = 4 \ln \left(\frac{N_a N_d}{n_i^2} \right)$
 Magnitude of the reverse-bias voltage is 7.18V ^{1/2}
 $E_m = \left[\frac{q(V_{bi} + V_r)}{d} \frac{N_a N_d}{(N_a + N_d)} \right]$

- Attempt the following questions: (1m)
 - Junction potential across a p-n junction (1m)
 - decreases with increasing doping concentration
 - increases with decreasing bandgap
 - does not depend on doping concentration
 - increases with increase in doping concentration
 - Justify that space-charge width increases (2m) with reverse-biased voltage in a pn junction diode.

- Turn over -
(2)

Q3 c) iii) For a Si pn junction at $T=300\text{K}$, (3m)
 $N_a = N_d = 10^{17}/\text{cm}^3$, $D_n = 25\text{cm}^2/\text{s}$, $D_p = 15\text{cm}^2/\text{s}$,
 $\tau_p = \tau_n = 5\text{ns}$.

Find value of reverse-saturation current (I_0)

OR

iii) Explain the deviations from ideal characteristics (I-V) in a p-n junction. Draw practical I-V curve. Explain the factors responsible for high-current in reverse-bias before breakdown. (3m)

$$I_0 = qA \left[\frac{D_p p_{n0}}{L_p} + \frac{D_n n_{p0}}{L_n} \right]$$

$$I_0 = qA n_i^2 \left[\frac{D_p}{L_p} \frac{1}{N_d} + \frac{D_n}{L_n} \frac{1}{N_a} \right]$$

$$L_p^2 = D_p \tau_p \Rightarrow L_p = \sqrt{D_p \tau_p} = \frac{8.66 \times 10^{-4}}{\text{cm}}$$

$$L_n^2 = D_n \tau_n \Rightarrow L_n = \sqrt{D_n \tau_n} = \frac{1.18 \times 10^{-3}}{\text{cm}}$$

$$I = I_0 \left(\exp \left(\frac{V_a}{V_T} \right) - 1 \right)$$

$$A = 10^{-4} \text{ m}^2$$

$$I_0 = 1.428 \times 10^{-15} \text{ A}$$